

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants : Kazuhide HASEBE, et al. **Confirmation No.: 6774**  
U.S. Serial No. : 10/552,262  
Filed : October 5, 2005  
Examiner : Lan Vinh  
Group Art Unit : 1792  
For : SILICON DIOXIDE FILM REMOVING METHOD AND  
PROCESSING SYSTEM

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed on November 20, 2008, for which the time for response is set to expire February 20, 2009, please amend the above-identified application as set forth below and consider the following remarks. Also enclosed is a Petition for a 2 month Extension of Time with the requisite fee.

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.